

	Hits	Search Text	DBs
55	56	((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (develop\$5 or TMAH)) and (UV near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5) near19 develop\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
56	48	((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (residu\$5 or remain\$5) same (develop\$5 or TMAH)) and (UV near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5) near19 develop\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
57	78	(UV near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5) near19 develop\$5 near12 (remov\$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
58	48	S63 NOT S62	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
59	53	S60 NOT S59	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
60	27	((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (develop\$5 or TMAH)) and ((UV near9 (laser or ablat\$4 or irradiat\$4)) same (resist or photoresist) same residu\$5 same develop\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
61	48	S63 NOT S60	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB